



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ko et al.

Serial No.: 09/711,324

Filed: November 13, 2000

For: ETCHANT WITH SELECTIVITY
FOR DOPED SILICON DIOXIDE OVER
UNDOPED SILICON DIOXIDE AND
SILICON NITRIDE, PROCESSES WHICH
EMPLOY THE ETCHANT, AND
STRUCTURES FORMED THEREBY

Confirmation No.: 7008

Examiner: K. Chen

Group Art Unit: 1765

Attorney Docket No.: 2269-3526.4US
(97-1136.05/US)

Notice of Allowance Mailed:

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AMENDMENT PURSUANT TO 37 C.F.R. § 1.312(a)

Mail Stop ISSUE FEE
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

Please amend the above-referenced application as follows:

Amendments to the Specification appear on page 3 of this paper.

Amendments to the Abstract appear on page 4 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 5 of this paper.

Remarks begin on page 11 of this paper.